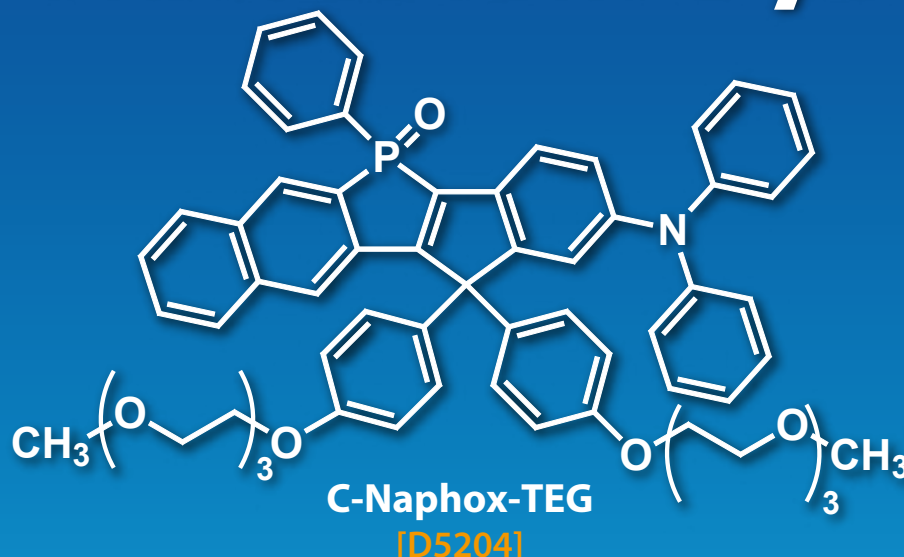


New

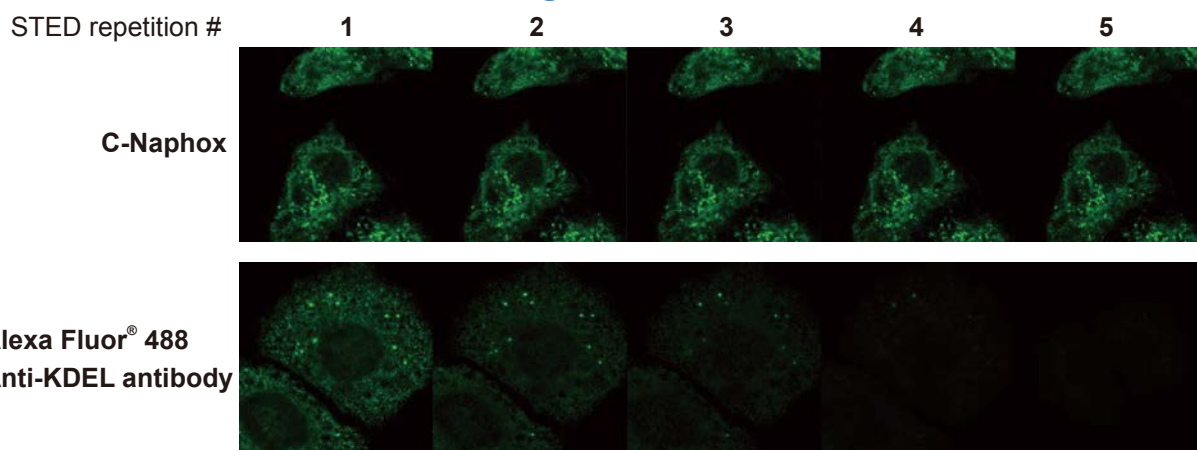
TCI[®]

Super Photoresistant Fluorescent Dye



STED (stimulated emission depletion) microscopy enables nanoscale visualization of biological systems. However, the intense laser beams for excitation and STED cause rapid photobleaching of fluorescent probe. C-Naphox-TEG is a fluorescent dye that exhibits outstanding photobleaching resistance even for repeated STED imaging.

STED Image of HeLa cells



Excitation: 488 nm, CW-STED: 592 nm
STED repetition: consecutively at 2 min 45 sec

D5204 C-Naphox-TEG (This product is only available in Japan.) 5mg JPY 20,000 / 25mg JPY 71,000

This product was produced by collaboration with Prof. Shigehiro Yamaguchi and Assoc. Prof. Aiko Fukazawa at Nagoya University.

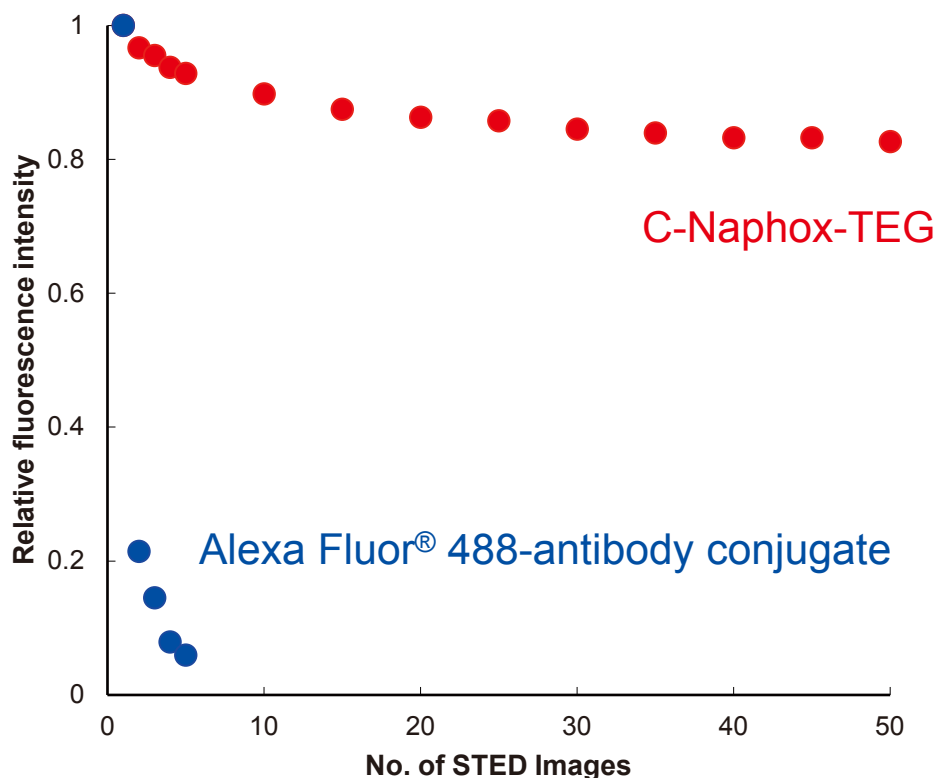
Reference

C. Wang, A. Fukazawa, M. Taki, Y. Sato, T. Higashiyama, S. Yamaguchi, *Angew. Chem. Int. Ed.* **2015**, 54, 15213.



Super Photoresistant Fluorescent Dye

Photostability of C-Naphox-TEG under STED conditions



Excitation: 488 nm, CW-STED: 592 nm

For further information please refer to our website at www.TCIchemicals.com.

fluorescent stain



TOKYO CHEMICAL INDUSTRY CO., LTD.

Sales Department Head Office

4-10-2 Nihonbashi-honcho, Chuo-ku, Tokyo 103-0023
TEL: 03-3668-0489
FAX: 03-3668-0520
E-mail: sales@TCIchemicals.com

Osaka Sales Office

Dai-Ni Nakai Bldg, 1-1-21, Kitahama, Chuo-ku, Osaka-shi, Osaka 541-0041
TEL: 06-6228-1155
FAX: 06-6228-1158
E-mail: osaka-s@TCIchemicals.com

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